

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:)	
)	
Wu et al.)	Group Art Unit: 2891
)	
Serial No.: 10/672,778)	Examiner: Smith, Bradley
)	
Filed: September 26, 2003)	Confirmation No.: 9717
)	
For: Atomic Layer Deposition (ALD) Method with)	TKHR Docket: 252016-3000
Enhanced Deposition Rate)	Top-Team: 0503-8501DUS
)	

AMENDMENT AND RESPONSE TO FINAL OFFICE ACTION WITH RCE

Mail Stop RCE
Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

The FINAL Office Action mailed May 19, 2006 has been carefully considered. In further response thereto, please enter the following amendments and consider the following remarks.